

LIST OF EXHIBITS

IPR2013-00363

ZEISS 1101	U.S. Patent No. 7,348,575 (“the Omura Patent”)
ZEISS 1102	U.S. Patent No. 7,309,870 (“the Omura ’870 Patent”)
ZEISS 1103	Judgment, Paper No. 49, Interference No. 105, 678 (“the ’678 Judgment”)
ZEISS 1104	Judgment, Paper No. 157, Interference No. 105, 749 (“the ’749 Judgment”)
ZEISS 1105	Judgment, Paper No. 41, Interference No. 105, 753 (“the ’753 Judgment”)
ZEISS 1106	Judgment, Paper No. 291, Interference No. 105, 834 (“the ’834 Judgment”)
ZEISS 1107	Certified English Translation of Japanese Unexamined Patent Publication No. JP 2003-128154
ZEISS 1108	Certified English Translation of Japanese Unexamined Patent Publication JP 2003-350647
ZEISS 1109	Certified English Translation of Japanese Unexamined Patent Publication JP 2003-364596
ZEISS 1110	US Patent Application Publication No.US 2005/0036213 (“Mann”)
ZEISS 1111	JP Patent Application Publication No. JP 2003-114387
ZEISS 1112	Certified English Translation of JP Patent Application Publication No. JP 2003-114387 (“Omura ’387”)
ZEISS 1113	PCT Patent Publication WO 02/035273 (“Takahashi PCT”)
ZEISS 1114	European Patent Application Publication No. EP 1 336 887 A1 (“Takahashi”)
ZEISS 1115	Satori Asai et al., “Resolution Limit for Optical Lithography Using Polarized Light Illumination,” Jpn. J. Appl. Phys. Vol. 32, pp. 5863-5866 (1993) (“Asai”)

ZEISS 1116	Expert Declaration of Richard C. Juergens
ZEISS 1117	Wikipedia, "Optical Power," https://en.wikipedia.org/wiki/Optical_power (downloaded May 20, 2013)
ZEISS 1118	Willi Ulrich et al., "The Development of Dioptric Projection Lenses for DUV Lithography," Proc. SPIE Vol. 4832, pp. 158-169 (2002) ("Ulrich")
ZEISS 1119	Eugene Hecht, <u>Optics</u> (4 th ed.), Addison Wesley (2002), pp. 171-173.
ZEISS 1120	Wikipedia, "Optical Axis," https://en.wikipedia.org/wiki/Optical_axis (downloaded May 20, 2013)
ZEISS 1121	New World Dictionary of the American Language, Second College Edition, p. 1552, Simon and Schuster (1980)
ZEISS 1122	File History Excerpts from U.S. Serial No. 11/266,288 ("Omura Application")
ZEISS 1123	US Patent No. 5,825,043 ("Suwa")
ZEISS 1124	Wikipedia, "Refractive Index," http://en.wikipedia.org/wiki/Refractive_index (downloaded May 20, 2013)
ZEISS 1125	U.S. Patent No. 4,346,164 ("Tabarelli")
ZEISS 1126	File History Excerpts from U.S. Serial No. 11/513,160 ("Omura Continuation Application")
ZEISS 1127	J.R. Sheats and B.W. Smith, <u>Microlithography: Science and Technology</u> , Marcel Dekker, Inc. (1998), Chapter 1, pp. 1-43.
ZEISS 1128	Omura Reply 1, Paper No. 200, Interference No. 105,834
ZEISS 1129	<i>Curriculum Vitae</i> of Richard C. Juergens
ZEISS 1130	CODE V Sequence Data
ZEISS 1131	CODE V Sub-routines
ZEISS 1132	OPTI 517 Lens Design Fall 2013

ZEISS 1133	OPTI 517 Image Quality
ZEISS 1134	U.S. Application No. 10/639,780 Mann Application
ZEISS 1135	Deposition of Richard Juergen in IPR2013-00363 Zeiss v. Nikon
ZEISS 1136	Transcript of May 8, 2014 Deposition of Jose Sasian, Ph.D.
ZEISS 1137	U.S. Application No. 12/379,415 as filed
ZEISS 1138	Office Action issued in U.S. Application No. 12/379,415 on January 7, 2011
ZEISS 1139	Amendment under 37 CFR 1.111 filed on U.S. Application No. 12/379,415 on July 7, 2011
ZEISS 1140	U.S. Patent No. 3,887,273 (“Griffiths”)
ZEISS 1141	U.S. Patent No. 4,867,551 (“Perera”)
ZEISS 1142	U.S. Patent No. 5,552,922 (“Margarill”)
ZEISS 1143	U.S. Patent No. 7,631,975 (“Takaura”)
ZEISS 1144	U.S. Patent No. 8,279,527 (“Lin”)
ZEISS 1145	<i>GE Lighting Solutions, LLC v. Agilight, Inc.</i> , No. 2013-1267, Slip. Op. 5 (Fed. Cir. May 1, 2014)